



# IEEE SW Test Workshop

## Semiconductor Wafer Test Workshop

June 8 - 11, 2014 | San Diego, California

# Key Considerations to Probe Cu Pillars in High Volume Production



GLOBALFOUNDRIES



FORMFACTOR INC.

Alexander Wittig (GLOBALFOUNDRIES)

Amy Leong, Tin Nguyen, Tommaso Masi,

Jarek Kister, Mike Slessor (Form Factor)

# Overview

- **Key Industry Trends**
- **Applying Lessons Learned from 100um Pitch CuP Production Probing to Optimize 80um Solution**
  - 3D Low-force (vertical & lateral probe force)
  - Alignment Control
  - Current Carrying Capability
  - Probe Assembly Throughput
- **Summary**

# Chapter 4 of Cu Pillar Probing Study



**IEEE SW Test Workshop**  
Semiconductor Wafer Test Workshop  
June 12 to 15, 2011  
San Diego, CA

**Evaluation of New Probe Technology on SnAg and Copper Bumps**

GLOBALFOUNDRIES Alexander Wittig (GLOBALFOUNDRIES)  
MICROPROBE Amy Leong (MicroProbe)  
NIKAD Darko Hulic (Nikad)

2011: 150um Pitch  
Cu Pillar Probing

**28nm Mobile SoC Copper Pillar Probing Study**

intel Jose Horas (Intel Mobile Communications)  
MICROPROBE Amy Leong (MicroProbe)  
NIKAD Darko Hulic (Nikad)

SWTW  
IEEE SW Test Workshop  
Semiconductor Wafer Test Workshop  
June 10 - 13, 2012 | San Diego, California

2012: 120um Pitch  
Cu Pillar Probing



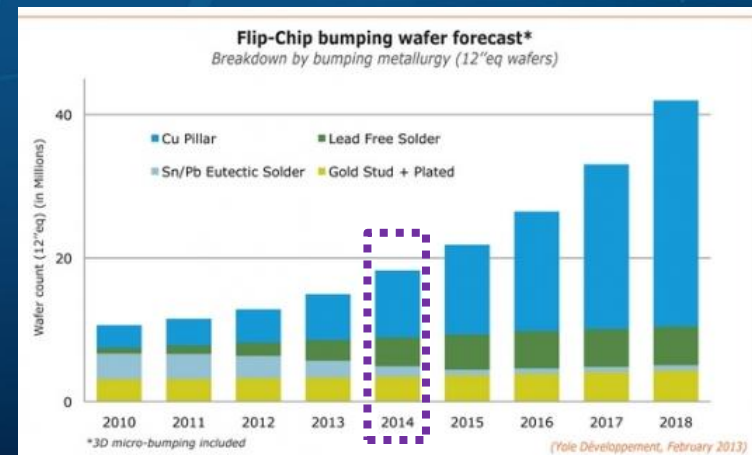
**IEEE SW Test Workshop**  
Semiconductor Wafer Test Workshop  
June 9 - 12, 2013 | San Diego, California

**Probing Study of Fine-pitch Copper Pillars**

GLOBALFOUNDRIES Alexander Wittig (Globalfoundries)  
FORMFACTOR Amy Leong, Tin Nguyen, Andrew McFarland, Mike Slessor (Form Factor)  
MICROPROBE Darko Hulic (Nikad)  
NIKAD

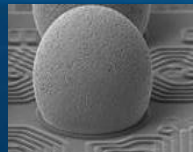
2013: 100um Pitch  
Cu Pillar Probing

- In 2014, Cu Pillar is becoming the mainstream flip-chip packaging technology (Source: Yole)
- Key issue is “How to best prepare for fine-pitch Cu Pillar probing in high volume production?”

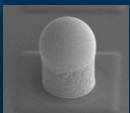


# Applying Lessons Learned from 100um Pitch CuP Production Probing to Optimize 80um Solution

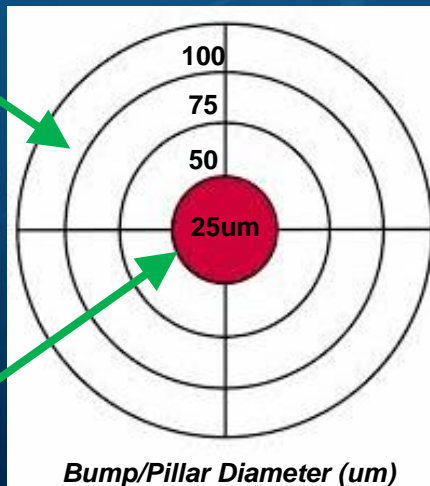
- Standard Cobra probes are vanishing for leading edge Cu Pillar (CuP) probing
- FormFactor has shipped >3000 units of CuP MEMS probe cards used in high volume production, hundreds of custom designs
  - CuP pitch ranges from 130um to 100um today, rapidly moving into 80um
  - CuP diameter shrinks accordingly from 70um to sub-30um
  - A typical probe card has 5,000 to 25,000 probes
- Many factors, which seem to be trivial for 150um pitch solder probing, need to be carefully considered when probing sub-100um pitch CuP in high volume production



150um Pitch Solder Bump



Sub-80um Pitch Cu Pillars



## Aiming Accuracy for 80um Grid-array Pitch CuP Probing in HVM

Hit The Bull's Eye  
100% Success Rate  
20,000+ Arrows Simultaneously

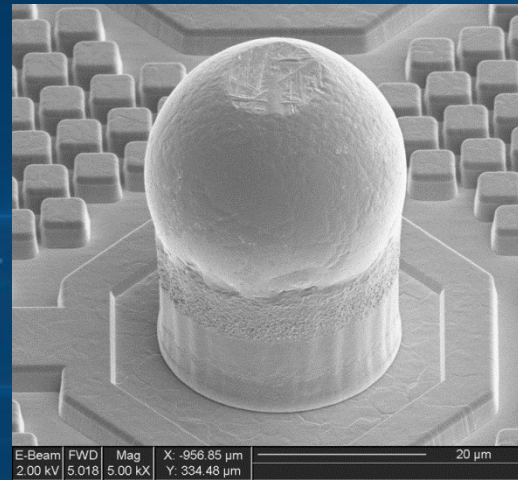
# HVM CuP Probing Essentials

## Key Differences Between Solder and CuP Probing

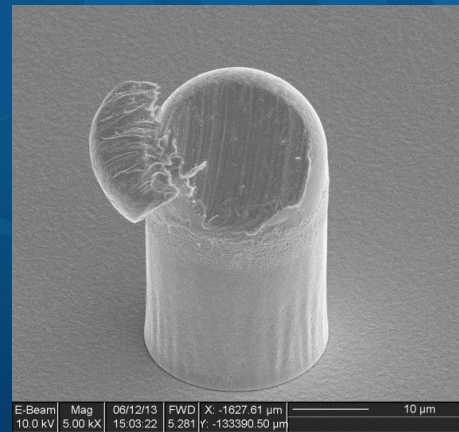
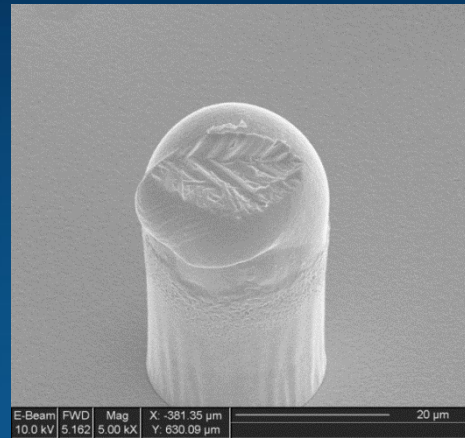
- **3D low-force probing and impact on probe marks**
  - z-force and x/y shear force
- **Probe-tip to Cu Pillar alignment**
  - What x/y alignment target is good enough?
  - Probe card x/y alignment, throughout the product life time
  - Operational optimization (Prober setup, cleaning, etc)
- **Current Carrying Capability @ Fine-Pitch**
- **Probe Assembly Throughput**



# Cu Pillar Probe Mark Photo Gallery



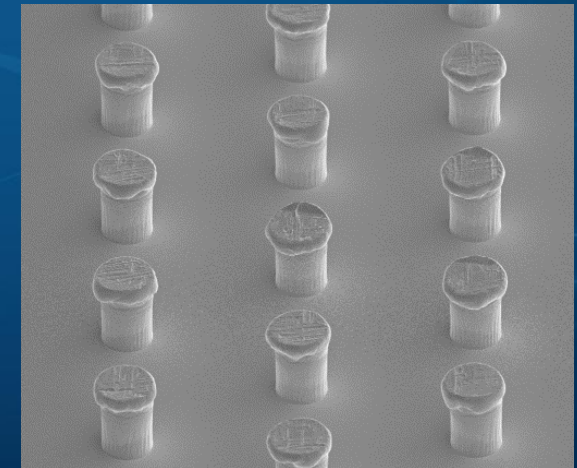
Pass  
Good Probe Mark on  
30um Cu Pillar



No Pass  
Cu Pillars with Sheared  
Solder Cap



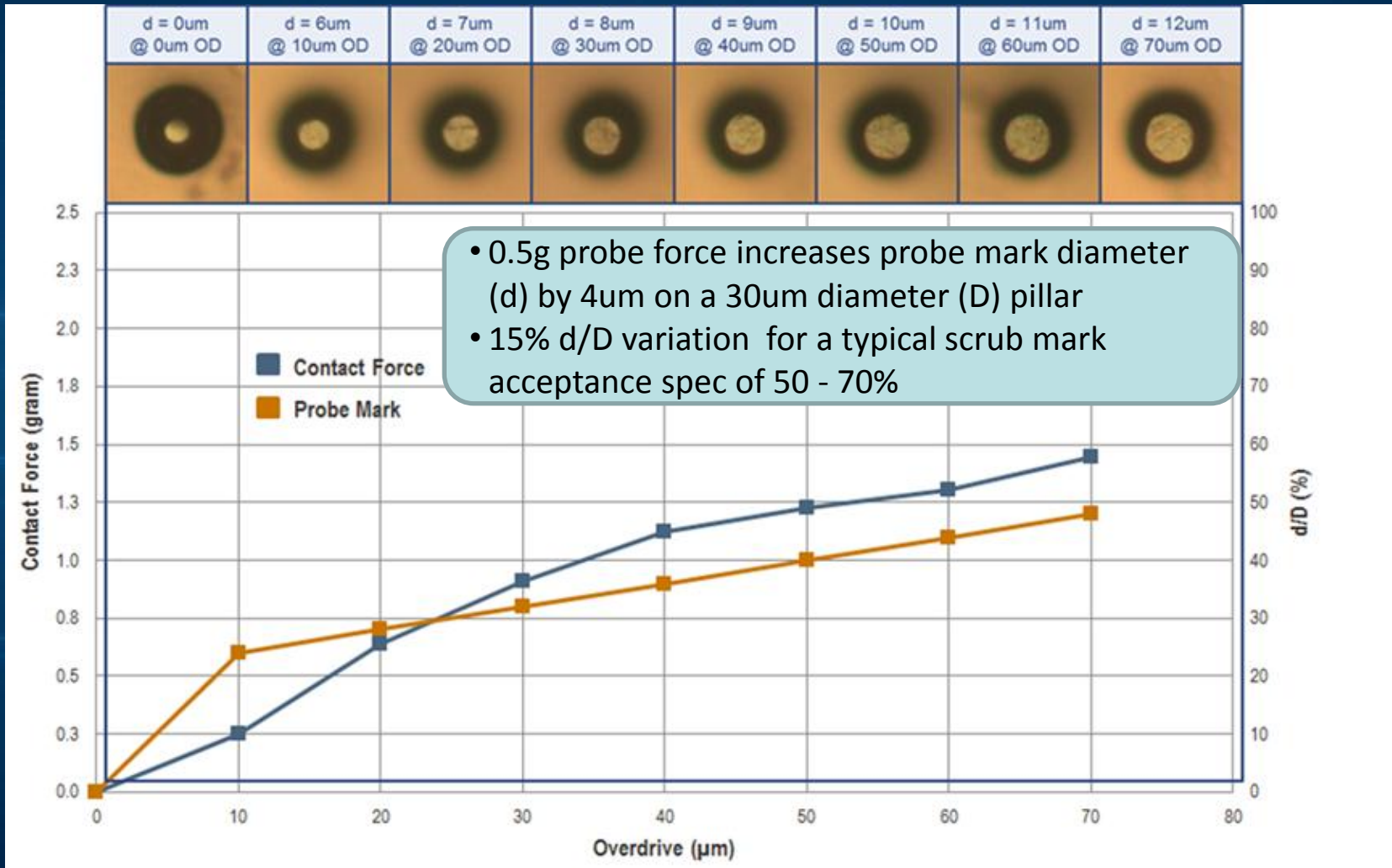
No Pass  
Misaligned Probe Tip



No Pass  
Probe force too high

# Impact of Z-force on Scrub Mark Size

Probe mark size is more sensitive to z-force @ 80um pitch



# FFI Shear Force Tool for CuP Wafer Characterization

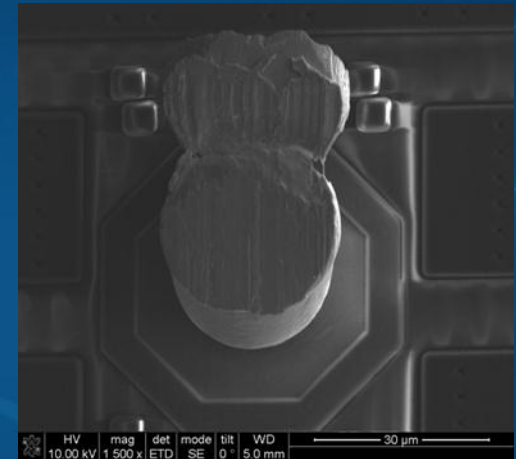
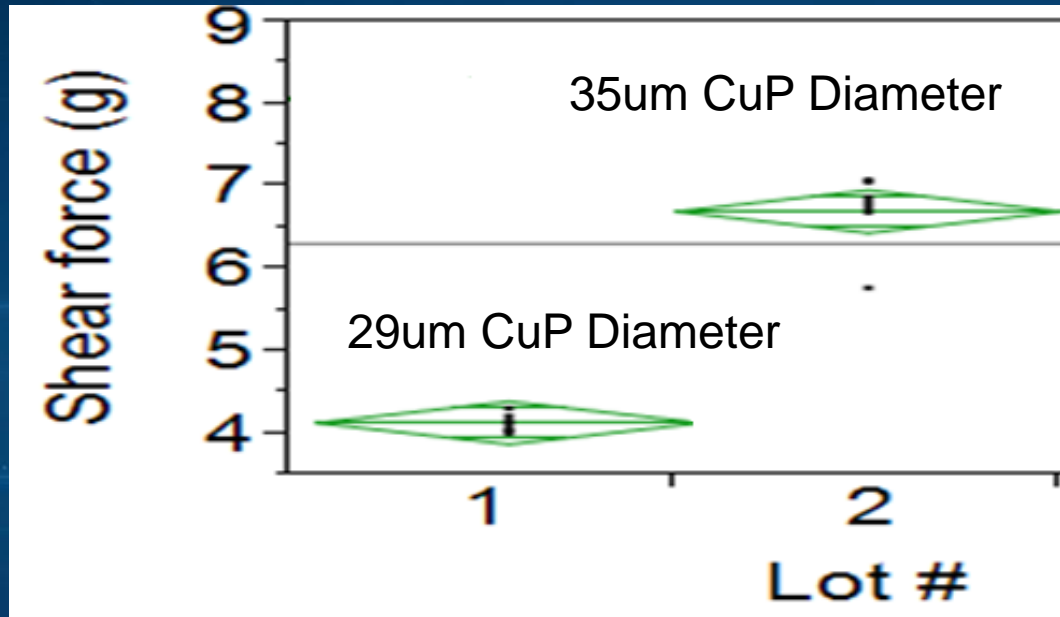
- FFI shear force measurement tool with ultra-fine stylus
- Stylus moves horizontally to push solder materials
- Shear force is measured as solder cap being displaced





# Solder Cap Destructive Shear Test Results

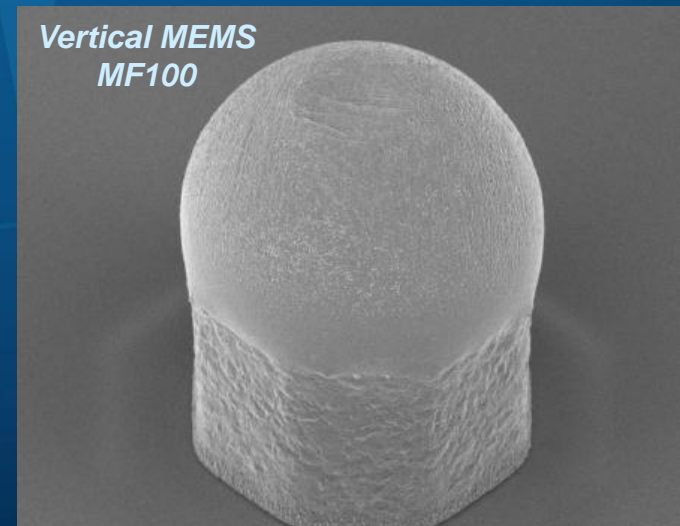
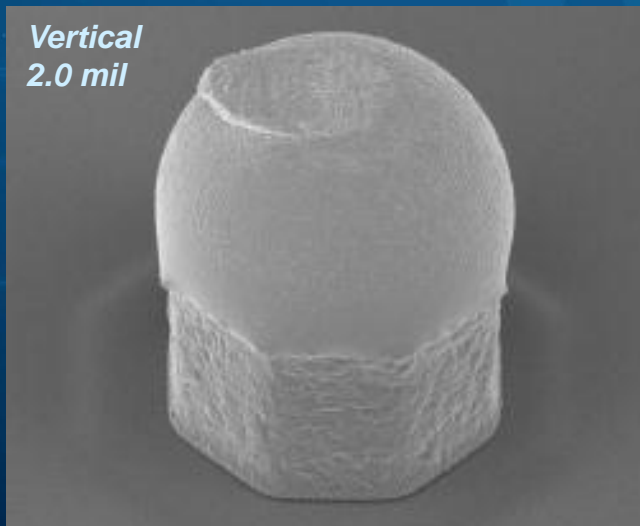
## Less solder volume, Easier to shear off the Cap



- Shear height =  $26\mu\text{m}$ , Shear velocity =  $50\mu\text{m/s}$
- 17% reduction in CuP diameter leads to  $\sim 40\%$  more fragile solder cap to lateral shear force

# Low Vertical & Lateral Probe Force is Essential To Probe 80um Pitch CuP in HVM to Ensure Packaging Reliability

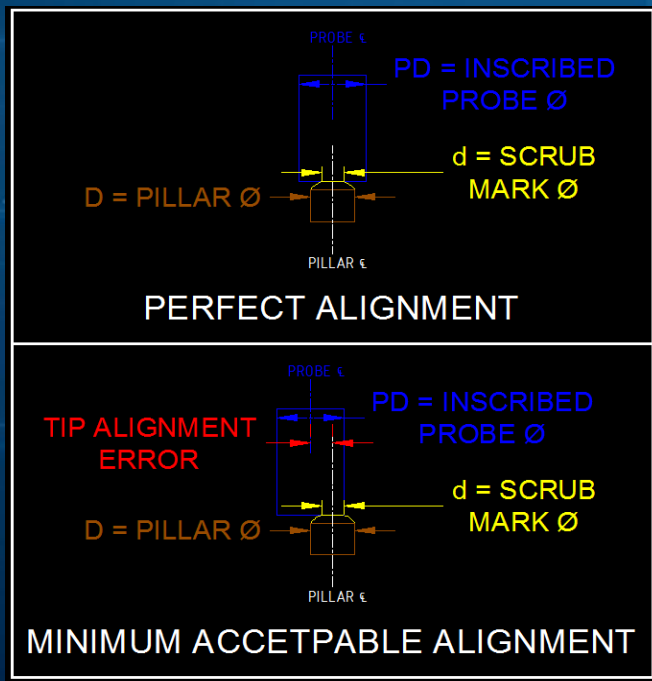
- Pictures below illustrate that 2 mil probe, with similar z-force but higher lateral force, induce more solder cap disturbance compared to a low-impact vertical MEMS probe (FormFactor's MF100)
- **Benefit of low-impact probing**
  - Minimizes solder material displacement on the solder surface
  - Eliminate the need for additional reflow post wafer probing (due to solder damage)
  - More even force at pillar footing for better packaging reliability



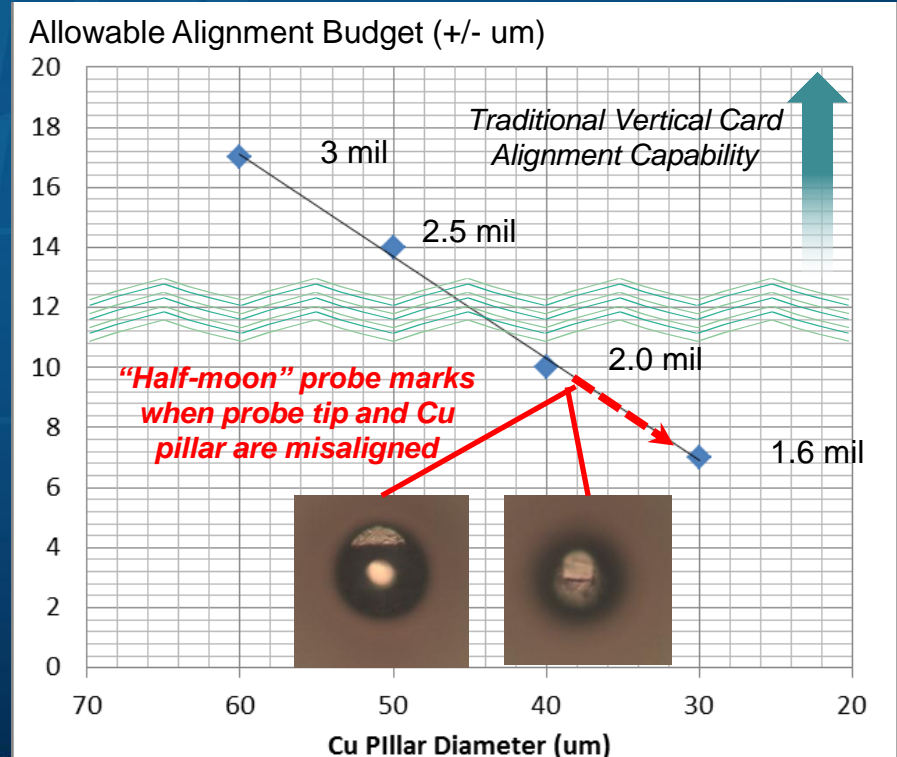
Probe Mark Comparison of Vertical MEMS MF100 vs. Vertical 2.0mil

# What is the allowable Probe tip-to-Cu Pillar Alignment Tolerance for CuP Probing in HVM?

- Really depends – Probe tip geometry relative to Cu Pillar diameter
- But for sure --- Allowable alignment budget between probe tip and Cu Pillar decreases as pitch and pillar diameter shrink

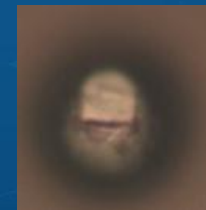
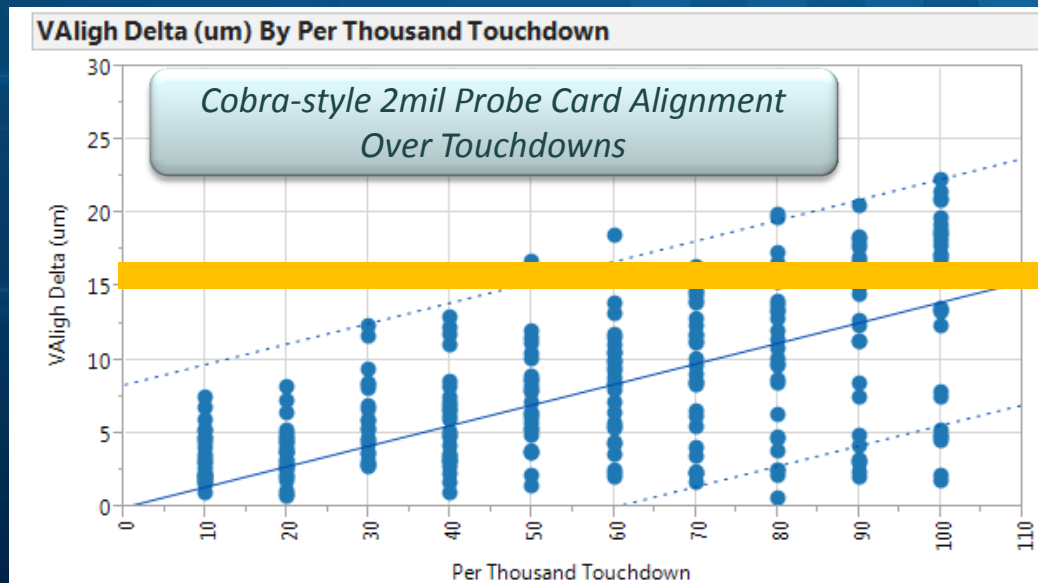


Source: SWTW 2013 Wittig



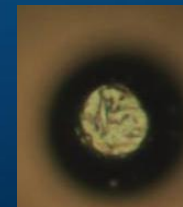
# Good Probe Tip-to-Cu Pillar Alignment is Crucial Not Just At The Beginning, But Also At the End of Life

- **Cobra-style vertical probe cards are good enough for larger pitch solder flip-chip probing**
  - Don't have to be super accurate to hit the "Dart Board"
- **For CuP production, probe tip-to-CuP alignment stability is crucial**
  - Aiming accuracy must be excellent to hit the "Bulls Eye"
- **Alignment maintenance challenges associated with cobra-style 2mil on 80um pitch CuP**
  - Cobra-style 2mil probe alignment was optimized initially to meet alignment requirement
  - After 40,000 touchdowns, probe tip x/y position began to drift outside the CuP alignment tolerance window
  - Frequent probe tip adjustment (tester down-time) or costly reflow would be needed



**No Pass**

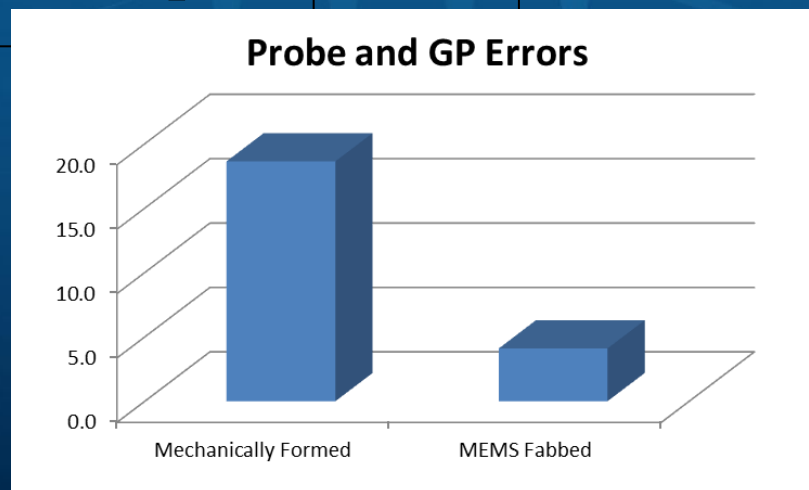
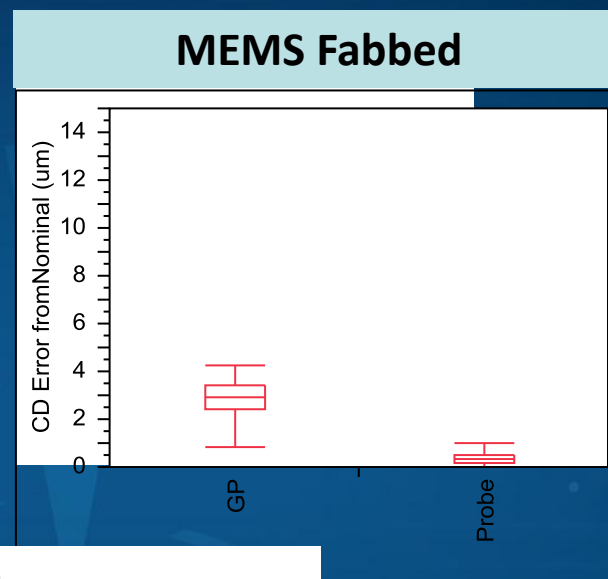
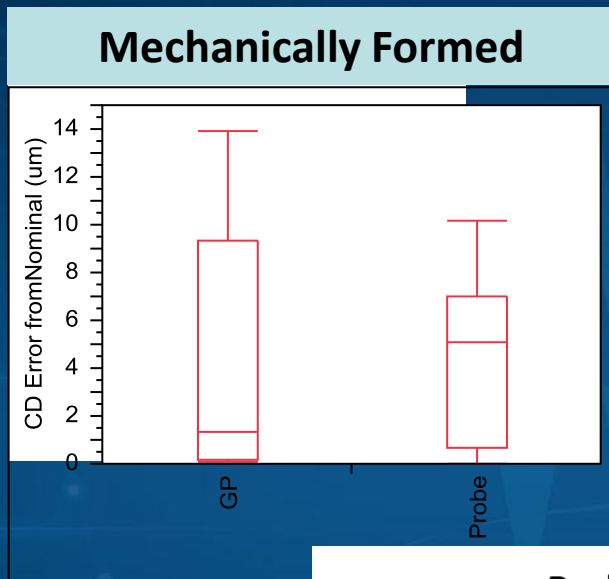
*Alignment accuracy needed to ensure acceptable scrub mark*



**Pass**



# Dimensional Control Improved With MEMS-Based Fabrication Processes



- Raw “as-fabbed” distributions
- Indicative of natural process capability

Source: SWTW 2013 Slessor

# Essential Factors to Improve Alignment for 80um Pitch CuP Probing in HVM

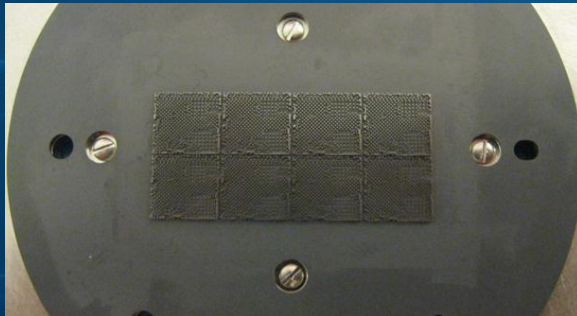
- **Factors to Consider to Maximize Production Uptime**

- **Prober Setup Optimization**: general algorithm for solder bump probing doesn't work any more
  - Fine-tune the probe-tip recognition alignment recipe to the specific probe type
  - Recognition of the bump needs to be tuned and developed, since the geometry of the Cu pillars are near the limit of the prober optics
  - Maximum allowable probe card planarity needs to be tightened
- **Probe Tip cleaning**: tip clean with minimal side movement
  - More gentle cleaning materials, i.e. 1um lapping film, as opposed to 3um
- **Probe Tip X/Y Positioning**: Well maintained x/y spec throughout lifetime
  - MEMS Probes with dimensional control ~5x improved over mechanical formed
  - MEMS formed guide-plates with position ~3X improved accuracy
  - Design and material selections of MEMS probes & guide-plates to minimize x/y positioning drift over life-time

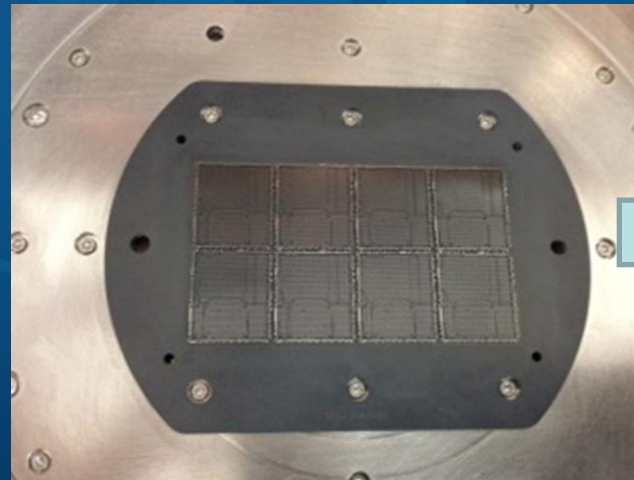
# 80um Pitch CuP Alignment Scalability

## For Multi-sites and Wider Temperature Testing

- Multi-sites testing will continue to drive up pin counts and probing active area
- Dual temperature probing, -40 to 90C



100um Pitch, 6k Pins  
30mm Diagonal Active Area

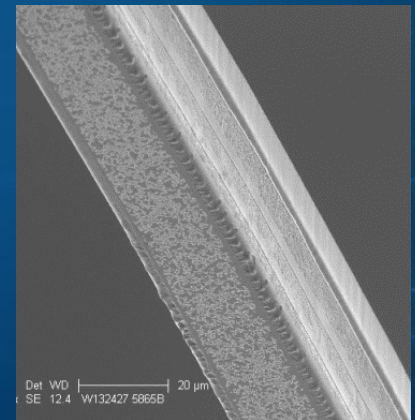
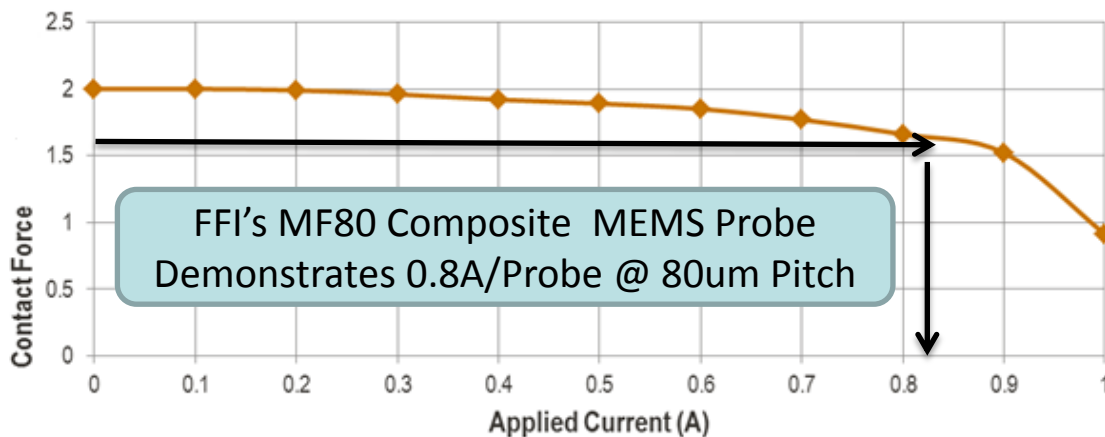


100um Pitch, 25k Pins,  
50mm Diagonal

80um Pitch, 30k Pins  
>60mm Diagonal

# Composite Material MEMS Probes Enables High Current-Carrying-Capability @ 80um Pitch

- Carrying more current through a smaller cross-Section @ 80um CuP pitch is challenging compared to larger probes @150um pitch
- Transient currents can be significantly higher than 0.5A/probe in HVM
- High CCC probe is essential to prevent probes degrade and get plastically deformed in the event of high transient current



Composite MF80 MEMS Probe with different materials, in different locations, with micron-level precision

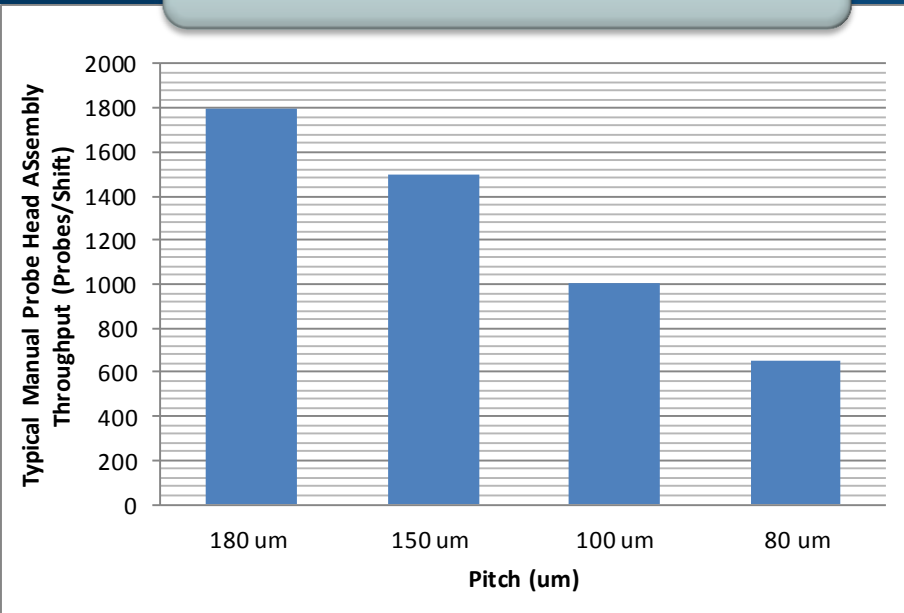


# Mechanically Formed Vertical Probes Give Way to MEMs Probes Below 100um Pitch

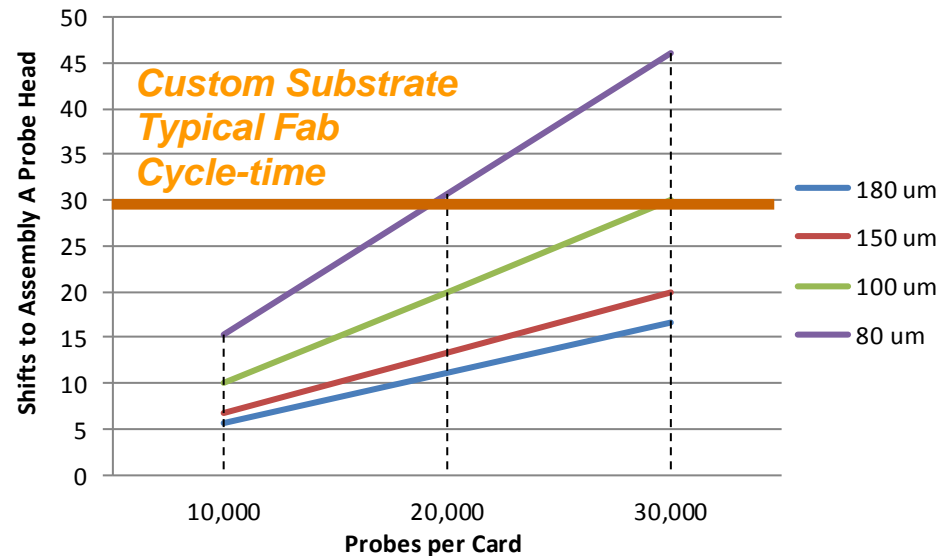
- Mechanical Tolerances for Stamped probes are inferior to MEMs structures
- Guide Plate Mechanical Drilling is Inferior to MEMs Guide Plate Formation Technology
- Tip Geometries are Poorly Controlled by Stamping and Forming Versus MEMs fabrication
- Contact Materials are Limited to Bulk Alloys for Mechanical Probes but are By Design for MEMs probes.
- Stable Contact at Low Probe Forces is Enabled by MEMs contact Design.

# Probe Assembly Throughput Is Becoming An Issue for Probe Card Cycle-time @ 80um CuP Pitch

Vertical Probe Assembly Throughput Decreases with Slimmer Probes



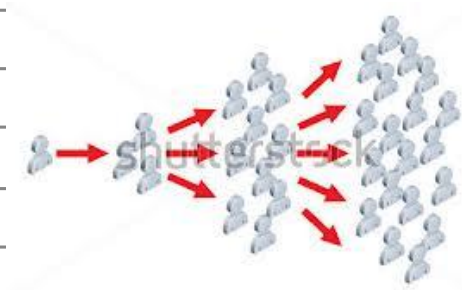
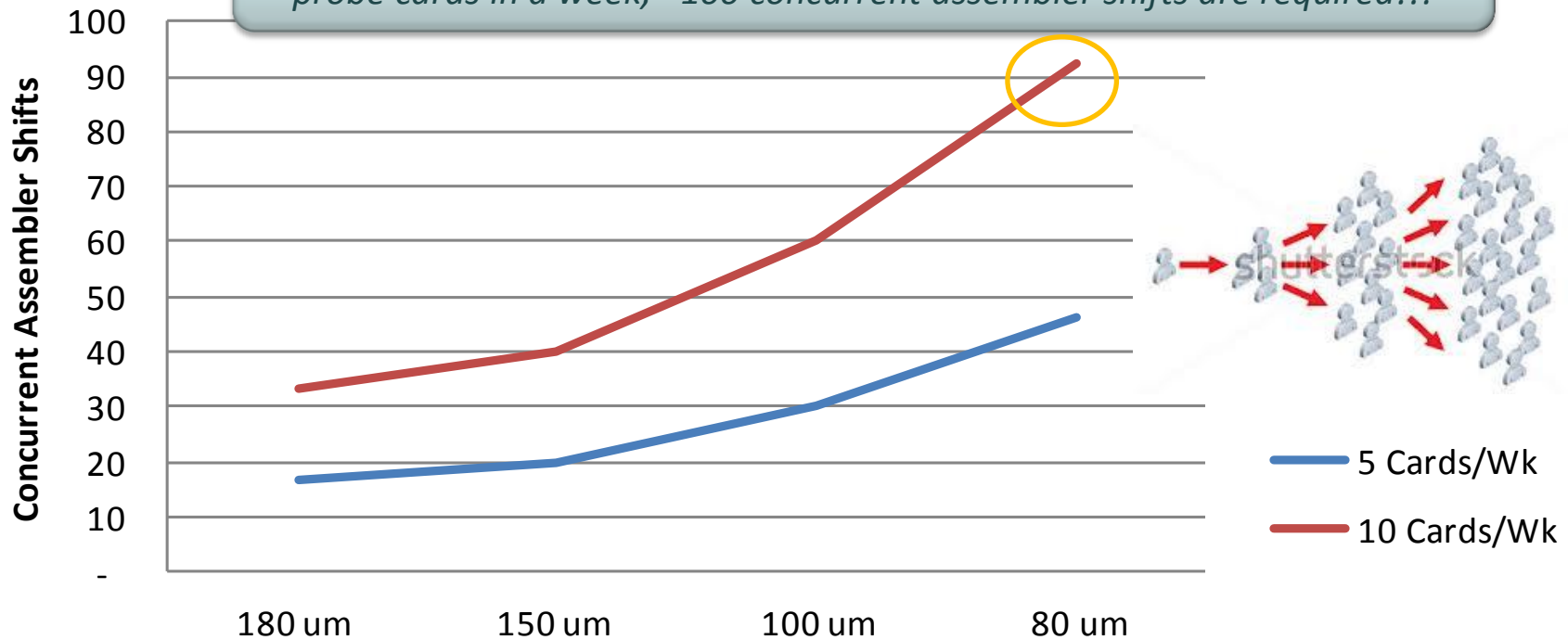
Probe Head Assembly Is Becoming the Critical Path to Probe Card Cycle-time As Pin Counts/Probe Card Approaches 20k Pins



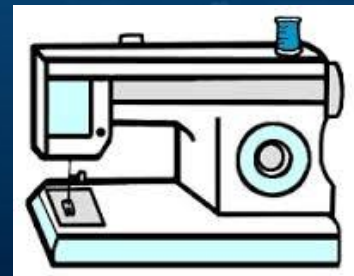
# Time-to-Volume Ramp-up @ 80um CuP Pitch

## What if 5 or 10 cards are needed in a week to address peak demand?

*With manual probe head assembly, to ship 10 units of 30k-pins 80um-pitch probe cards in a week, ~100 concurrent assembler shifts are required!!!*



*"Hand to Machine" Conversion Begins @ 80um Grid-array CuP Pitch*



# Summary

- **Static trend of grid-array packaging pitch is turning into rapid reduction with Cu Pillar Technology**
  - 150um -> 130um -> 100 -> 80um -> sub-50um
- **Conventional technology can't keep up with the current trend**
  - 3D Low-force, Alignment, Current Carrying Capability, Assembly Method
- **MEMS probe contact technology is required to keep up with the rapid pitch reduction, while keeping sanity and peace in HVM**
  - Many HVM wisdoms for probing solder bumps no longer work for CuP
  - Close collaboration among users, test cell and probe card suppliers is essential
- **“Hand to Machine” probe assembly conversion begins at 80um grid-array pitch CuP HVM**

